

Notice of References Cited	Application/Control No. 10/534,199	Applicant(s)/Patent Under Reexamination ASPAR ET AL.	
	Examiner Bradley K. Smith	Art Unit 2894	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Venzia et al. "The role of implantation damage in the production of silicon-on-insulator films by co-implantation of He+ and H+" Proc. of Eighth Int'l Symposium on Silicon Materials Science and Technology, 1998.
	V	
	W	
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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